ABSTRACT

SUBSTRATE HOLDING DEVICE,EXPOSURE APPARATUS HAVING SAME, EXPOSURE METHOD, METHOD FOR PRODUCING DEVICE, AND LIQUID REPELLENT PLATE

A substrate holder (PH) includes a base (PHB); a first holding portion (PH1) which is formed on the base (PHB) and which attracts and holds a substrate (P); and a second holding portion (PH2) which is formed on the base (PHB) and which attracts and holds a plate member (T) in the vicinity of the substrate (P) attracted and held by the first holding portion (PH1). In an exposure apparatus including such a substrate holder (PH), the plate can be exchanged easily, thereby making the maintenance of the apparatus easy. Consequently, such an exposure apparatus is suitable for immersion exposure.

[FIGURE 2]